

ABSTRACT

To provide a sputtering target for magnetic materials, a sputtering target assembly for magnetic materials, and a method for producing a sputtering target for magnetic materials that can effectively suppress peeling of a redeposited film.

The sputtering target for magnetic materials has a sputtering region and a non-sputtering region, wherein a surface of the non-sputtering region has a plurality of rounded convex portions, wherein the plurality of convex portions include convex portions connected via connecting portions and/or convex portions not connected via connecting portions.